Art Unit: 2800

Clmpto 10042005 PY

11. (Previously presented) A quantum tunneling device formed in accordance with a method comprising the steps of:

providing a quantum well, said quantum well comprising a composite material, said composite material comprising at least a first and a second material; and processing said quantum well so as to form at least one segregated quantum tunneling structure encased within a shell comprised of a material arising from processing said composite material, wherein each said segregated quantum structure is substantially comprised of said first material.

20. (Previously presented) A quantum tunneling device formed in accordance with a method comprising the steps of:

from processing said first material.

providing a quantum well, said quantum well comprising at least three layers, each of said at least three layers comprising a first material, wherein at least one of said at least three layers additionally comprises at least a second material; and processing said quantum well so as to form at least one segregated quantum structure comprising at least said second material encased in a material arising

Best Available Copy

Art Unit: 2800

39. (Previously presented) A quantum tunneling device formed in accordance with a method comprising the steps of:

growing a quantum well on a substrate, said quantum well comprising at least a first material and a second material; patterning a mask on said quantum well; etching said quantum well so as to form a pillar; and processing said pillar so as to convert said first material thereby forming an altered first material and causing said second material to form at least one segregated quantum structure embedded in said altered first material.

40. (Original) A quantum tunneling device comprising:

at least one segregated quantum structure; and
a casing of a first material encapsulating said at least one segregated quantum
structure, wherein said casing is sufficiently thin so as to permit quantum
tunneling of electrons from a first segregated quantum structure to a structure
selected form the group consisting of segregated quantum structures and
electrodes.

41. (Original) The quantum tunneling device according to claim 40 wherein said at least one segregated quantum structure has a diameter of less than about 200 nanometers.

Art Unit: 2800

42. (Original) The quantum tunneling device according to claim 40 wherein said at least one segregated quantum tunneling structure has a diameter of less than about 50 nanometers.

- 43. (Original) The quantum tunneling device according to claim 40 wherein said segregated quantum structure comprises a material selected from the group consisting of silicon, germanium, carbon, tin, gallium, arsenic, indium, aluminum, phosphorus, boron, antimony, nitrogen, zinc, sulfur, selenium, tellurium, cadmium, mercury, lead, and mixtures thereof.
- 44. (Original) The quantum tunneling device according to claim 40 wherein said first material comprises a material selected from the group consisting of silicon, germanium, carbon, tin, gallium, arsenic, indium, aluminum, phosphorus, antimony, nitrogen, zinc, sulfur, selenium, tellurium, cadmium, mercury, and mixtures thereof.
- 45. (Original) The quantum tunneling device according to claim 40 wherein said first material has been altered by a process selected from the group consisting of oxidation, reduction, and nitridation.
- 48. (Original) The quantum tunneling device according to claim 40 wherein said first material comprises a semi-conductive material selected from the group consisting of elements of group IIA of the periodic table, elements of group IIIA of the periodic table,

Art Unit: 2800

elements of group IVA of the periodic table, elements of group VA of the periodic table, elements of group VIA of the periodic table, and mixtures thereof.

47. (Original) The quantum tunneling device according to claim 40 wherein said quantum tunneling device has no dimension greater than 500 nanometers.

48. (Original) The quantum tunneling device according to claim 40 wherein said casing is substantially non-crystalline.

49. (Original) The quantum tunneling device according to claim 40 wherein said at least one segregated quantum structure is substantially crystalline.

51. (Original) An electronic device comprising:

a quantum tunneling device, said quantum tunneling device comprising at least one segregated quantum structure and a casing of a first material encapsulating said at least one segregated quantum structure; and

Art Unit: 2800

at least one electrode, wherein said casing is sufficiently thin so as to permit quantum tunneling of electrons from a segregated quantum structure to said at teast one said electrode.

- 62. (Original) The electronic device according to claim 51 wherein each said segregated quantum structure has a diameter less than about 200 nanometers.
- 53. (Original) The electronic device according to claim 51 wherein each said segregated quantum structure has a diameter less than about 100 nanometers.
- 64. (Original) The electronic device according to claim 51 wherein each said segregated quantum structure has a diameter not exceeding about 25 nanometers.
- 55. (Original) The electronic device according to claim 51 wherein said segregated quantum structure comprises a material selected from the group consisting of silicon, germanium, carbon, tin, gallium, arsenic, indium, aluminum, phosphorus, boron, antimony, nitrogen, zinc, sulfur, selenium, tellurium, cadmium, mercury, lead, and mixtures thereof.
- 56. (Original) The electronic device according to claim 51 wherein said first material comprises a material selected from the group consisting of silicon, germanium, carbon, tin, gallium, arsenic, indium, aluminum, phosphorus, boron, antimony, nitrogen, zinc, sulfur, selenium, tellurium, cadmium, mercury, lead, and mixtures thereof.

Art Unit: 2800

57. (Original) The electronic device according to claim 51 wherein said first material comprises a semi-conductive material selected from the group consisting of elements of group IIA of the periodic table, elements of group IVA of the periodic table, elements of group IVA of the periodic table, elements of group VA of the periodic table, elements of group VIA of the periodic table, and mixtures thereof.

58. (Original) The electronic device according to claim 51 wherein said first material has been altered by a process selected from the group consisting of oxidation, reduction, and nitradation.

59. (Original) The electronic device according to claim 51 wherein said at least one electrode comprises a material selected from the group consisting of lithium, beryllium, boron, carbon, nitrogen, oxygen, aluminum, silicon, calcium, titanium, vanadium, manganese, iron, cobalt, nickel, copper, zinc, gallium, germanium, arsenic, yttrium, zirconium, nlobium, molybdenium, palladium, silver, cadmium, indium, tin, antimony, barlum, tantalium, tungsten, tridium, platinum, gold, mercury, thallium, lead, bismuth, and mixtures thereof.

60. (Original) The electronic device according to claim 51 wherein said segregated quantum structure is substantially crystalline.

61. (Original) The electronic device according to claim 51 wherein said casing is substantially non-crystalline.

62. (Original) The electronic device according to claim 51 wherein said electronic device is operational at temperatures in excess of about 1K.

63. (Original) The electronic device according to claim 51, wherein said electronic device is operational at temperatures in excess of about 200K.

This Page is Inserted by IFW Indexing and Scanning Operations and is not part of the Official Record

BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images include but are not limited to the items checked:
☐ BLACK BORDERS
☐ IMAGE CUT OFF AT TOP, BOTTOM OR SIDES
☐ FADED TEXT OR DRAWING
☐ BLURRED OR ILLEGIBLE TEXT OR DRAWING
☐ SKEWED/SLANTED IMAGES
☐ COLOR OR BLACK AND WHITE PHOTOGRAPHS
☐ GRAY SCALE DOCUMENTS
☐ LINES OR MARKS ON ORIGINAL DOCUMENT
REFERENCE(S) OR EXHIBIT(S) SUBMITTED ARE POOR QUALITY

IMAGES ARE BEST AVAILABLE COPY.

As rescanning these documents will not correct the image problems checked, please do not report these problems to the IFW Image Problem Mailbox.